Electronic Supplementary Information
for

Healing Surface Roughness of Lithographic Nanopatterns through Sub-10 nm Aqueous-soluble Polymeric Particles with Excellent Dry Etch Durability

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Supplementary figures

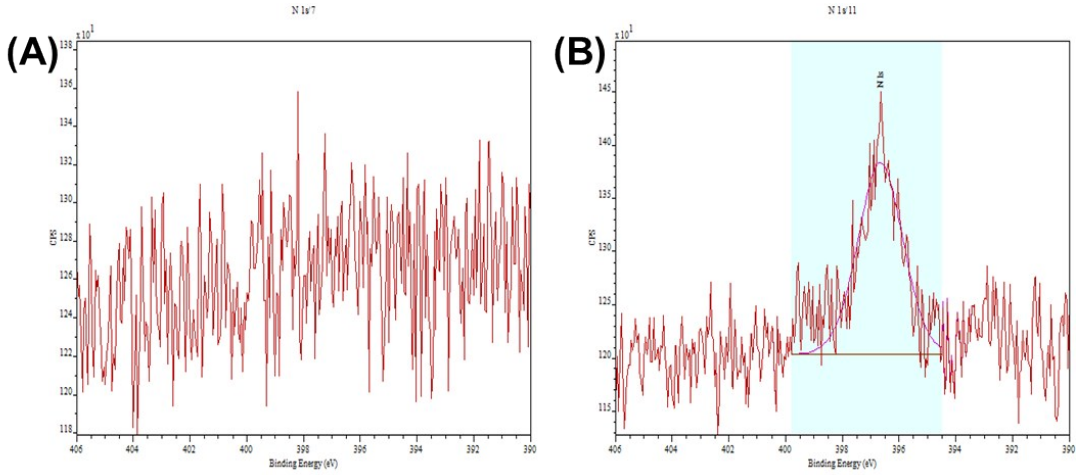

Figure S1. The high-resolution N1s XPS spectra of the model negatively charged surface before (A) and after (B) deposition of the micelles.

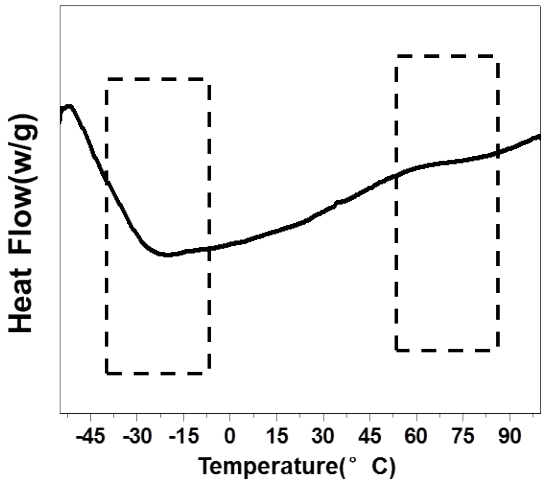

Figure S2. DSC traces for BCP-A1. Two distinct transitions at around -27°C and 53°C are observed.

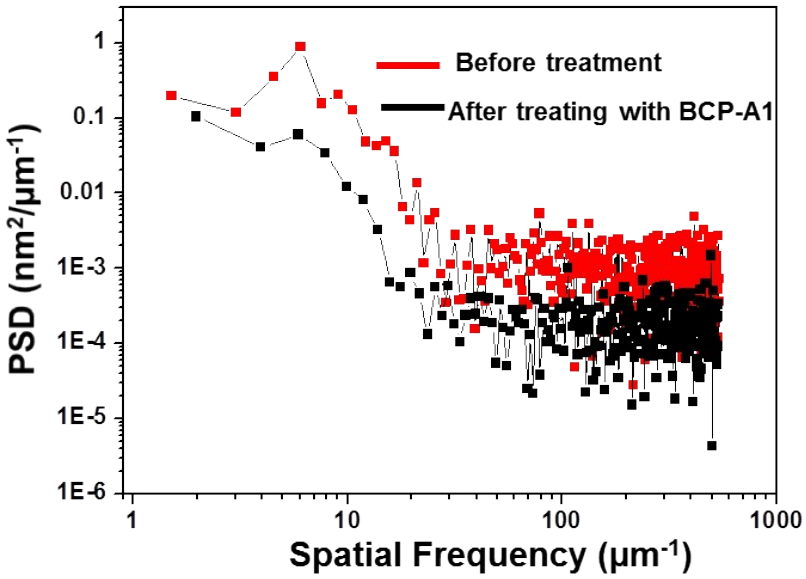

Figure S3. Power spectral density (PSD) functions for the patterned TER60 resist and those further treated with BCP-A1.

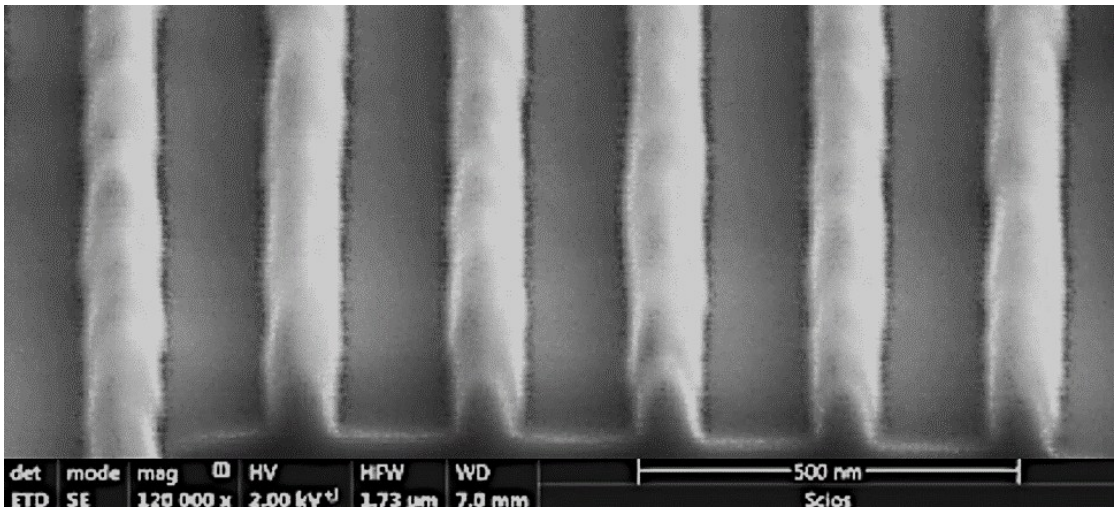

Figure S4. Cross-sectional SEM image after Si etching using TER EBL patterns template.

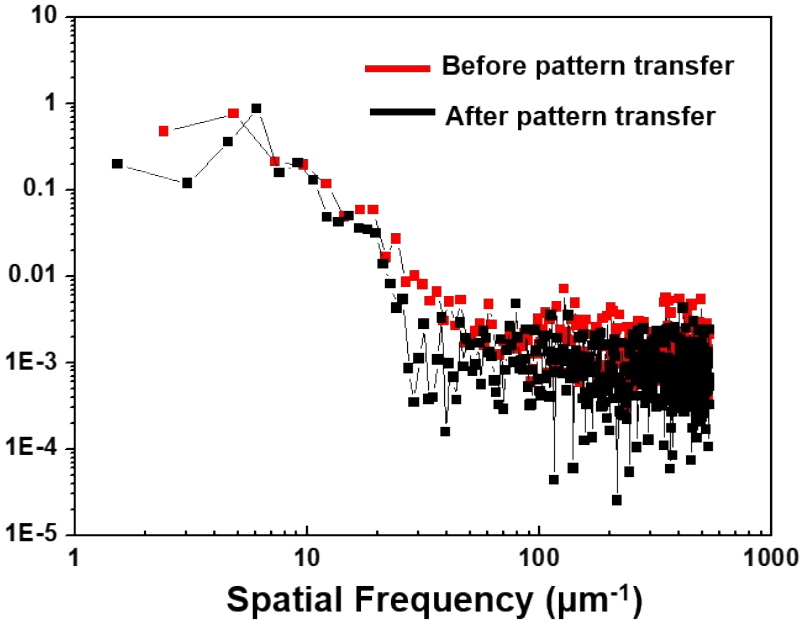

Figure S5. Power spectral density (PSD) functions for the patterned TER60 resist before and after pattern transfer.